



# 제 29회 한국반도체학술대회

The 29th Korean Conference on Semiconductors

2022년 1월 24일(월)~ 26일(수) | 강원도 하이원 그랜드호텔(컨벤션타워)

2022년 1월 25일(화), 10:45-12:30

Room B (에메랄드 II+III, 5층)

## D. Thin Film Process Technology 분과

### [TB2-D] Area-selective Growth

좌장: 김우희 교수(한양대학교), 김정환 교수(한밭대학교)

<p><b>TB2-D-1</b> 10:45-11:15</p>	<p><b>Fundamentals of Bottom-up Fabrication of Selective Patterns for Semiconductor Devices</b> Il-Kwon Oh <i>Department of Electrical and Computer Engineering, Ajou University</i></p>
<p><b>TB2-D-2</b> 11:15-11:30</p>	<p><b>Inherently Area-Selective Atomic Layer Deposition of Device-Quality <math>\text{Hf}_{1-x}\text{Zr}_x\text{O}_2</math> Thin Films through Catalytic Local Activation</b> Hyo-Bae Kim, Jeong-Min Lee, Woo-Hee Kim, and Ji-Hoon Ahn <i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p><b>TB2-D-3</b> 11:30-11:45</p>	<p><b>Inhibitor-Free Area-Selective Atomic Layer Deposition of <math>\text{SiO}_2</math> through Chemoselective Adsorption of an Aminodisilane Precursor on Oxide versus Nitride Substrates</b> Jeong-Min Lee<sup>1</sup>, Jinseon Lee<sup>1</sup>, Hongjun Oh<sup>2</sup>, Bonggeun Shong<sup>2</sup>, Tae Joo Park<sup>1</sup>, and Woo-Hee Kim<sup>1</sup> <sup>1</sup><i>Department of Materials Science and Chemical Engineering, Hanyang University,</i> <sup>2</sup><i>Department of Chemical Engineering, Hongik University</i></p>
<p><b>TB2-D-4</b> 11:45-12:00</p>	<p><b>Area-Selective Atomic Layer Deposition of <math>\text{HfO}_2</math> for RRAM Device Fabrication</b> Chae-Young Song, Ae-Rim Choi, and Il-Kwon Oh <i>Department of Electrical and Computer Engineering, Ajou University</i></p>
<p><b>TB2-D-5</b> 12:00-12:15</p>	<p><b>Small Precursor Inhibitors for Area Selective Deposition of Ru on Cu and <math>\text{SiO}_2</math></b> Sumaira Yasmeen, Bon Wook Gu, Minsung Kim, Young Ho Kang, and Han-Bo-Ram Lee <i>Incheon National University</i></p>
<p><b>TB2-D-6</b> 12:15-12:30</p>	<p><b>Area-Selective Atomic Layer Deposition of <math>\text{SiO}_2</math> Thin Films to Confer Oxide Versus Nitride Selectivity</b> Jinseon Lee<sup>1</sup>, Jeong-Min Lee<sup>1</sup>, Hongjun Oh<sup>2</sup>, Bonggeun Shong<sup>2</sup>, Tae Joo Park<sup>1</sup>, and Woo-Hee Kim<sup>1</sup> <sup>1</sup><i>Hanyang University,</i> <sup>2</sup><i>Hongik University</i></p>